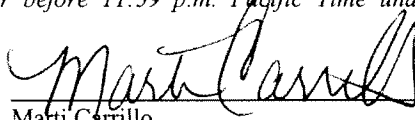


PATENT

Date of Notice  
of Allowance : December 19, 2008

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

*I hereby certify that this correspondence is being electronically filed with the United States Patent and Trademark Office on March 17, 2009 at or before 11:59 p.m. Pacific Time under the Rules of 37 CFR § 1.8.*

  
Marti Carrillo

Applicant : Kim, Nam Hun Confirmation No. 5813  
Application No. : 10/593,857  
Filed : September 22, 2006  
Title : PLASMA CHAMBER HAVING PLASMA SOURCE COIL AND  
METHOD FOR ETCHING THE WAFER USING THE SAME  
Grp./Div. : 1792  
Examiner : Duy Vu Nguyen Deo  
Docket No. : 58409/N305

**COMMENTS ON STATEMENT OF REASONS FOR ALLOWANCE**

Mail Stop Issue Fee  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Post Office Box 7068  
Pasadena, CA 91109-7068  
March 17, 2009

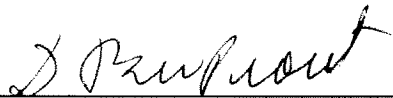
Commissioner:

Reasons for allowance are only warranted in instances in which "the record of the prosecution as a whole does not make clear his or her reasons for allowing a claim or claims."  
(37 CFR § 1.104(e))

Applicant believes the Examiner's stated reasons for allowance are unnecessary. The applicant does not necessarily agree with each statement in the reasons for allowance. While applicant agrees that the claims are allowable, applicant does not acquiesce with each statement in the reasons for allowance, that patentability requires each stated feature exactly as expressed by the Examiner, nor that each stated feature is required for patentability.

**Appln No. 10/593,857**  
**Stmt date March 17, 2009**

Respectfully submitted,  
CHRISTIE, PARKER & HALE, LLP

By   
D. Bruce Prout  
Reg. No. 20,958  
626/795-9900

DBP/mac

MAC PAS841388.1-\*03/17/09 11:23 AM